Atmospheric pressure plasma jet processed reduced graphene oxides for supercapacitor application

Fei-Hong Kuok, Chen-Yu Liao, Ting-Hao Wan, Po-Wei Yeh, I-Chun Cheng, Jian-Zhang Chen

PII: S0925-8388(16)32790-6

DOI: 10.1016/j.jallcom.2016.09.056

Reference: JALCOM 38890

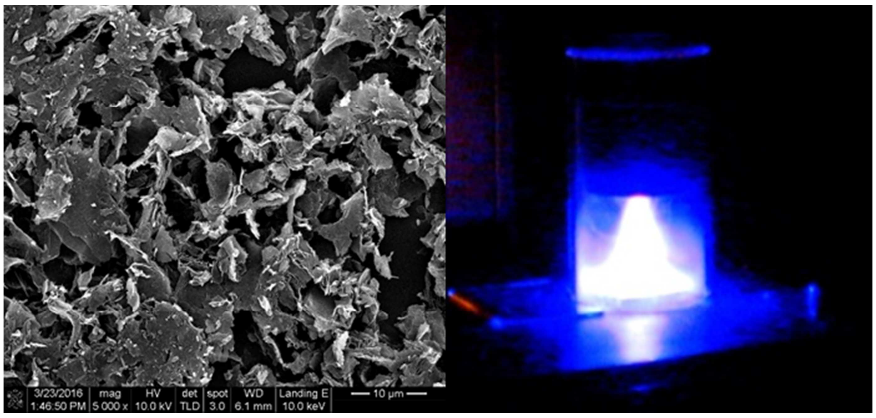
To appear in: *Journal of Alloys and Compounds*

Received Date: 16 June 2016

Revised Date: 23 August 2016

Accepted Date: 5 September 2016

Please cite this article as: F.-H. Kuok, C.-Y. Liao, T.-H. Wan, P.-W. Yeh, I.-C. Cheng, J.-Z. Chen, Atmospheric pressure plasma jet processed reduced graphene oxides for supercapacitor application, *Journal of Alloys and Compounds* (2016), doi: 10.1016/j.jallcom.2016.09.056.


3/23/2016
1:46:50 PM
mag
5 000 x
HV
10.0 kV
det
TLD
spot
3.0
WD
6.1 mm
Landing E
10.0 keV
10 µm